

# Nicholas C Strandwitz

## List of Publications by Year in descending order

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Version: 2024-02-01

18  
papers

346  
citations

1307594

7  
h-index

888059

17  
g-index

18  
all docs

18  
docs citations

18  
times ranked

691  
citing authors

#	ARTICLE	IF	CITATIONS
1	Interfacial band-edge energetics for solar fuels production. Energy and Environmental Science, 2015, 8, 2851-2862.	30.8	163
2	Highly Oriented MoS <sub>2</sub> Coatings: Tribology and Environmental Stability. Tribology Letters, 2016, 64, 1.	2.6	37
3	cm <sup>2</sup> -Scale Synthesis of MoTe <sub>2</sub> Thin Films with Large Grains and Layer Control. ACS Nano, 2021, 15, 410-418.	14.6	27
4	Aluminum Oxide Passivating Tunneling Interlayers for Molybdenum Oxide Hole-Selective Contacts. IEEE Journal of Photovoltaics, 2020, 10, 722-728.	2.5	25
5	Cyclic azasilanes as volatile and reactive precursors for atomic layer deposition of silicon dioxide. Journal of Materials Chemistry C, 2016, 4, 4034-4039.	5.5	20
6	Wear behavior of annealed atomic layer deposited alumina. Wear, 2017, 372-373, 139-144.	3.1	17
7	Plasma-enhanced atomic layer deposition of titanium vanadium nitride. Journal of Vacuum Science and Technology A: Vacuum, Surfaces and Films, 2018, 36, .	2.1	12
8	Absence of Evidence for Fixed Charge in Metal-Aluminum Oxide-Silicon Tunnel Diodes. Physica Status Solidi (B): Basic Research, 2019, 256, 1800342.	1.5	7
9	Plasma-enhanced atomic layer deposition of vanadium nitride. Journal of Vacuum Science and Technology A: Vacuum, Surfaces and Films, 2019, 37, .	2.1	6
10	Electrical properties of MgO/GaN metal-oxide-semiconductor structures. Solid-State Electronics, 2020, 172, 107881.	1.4	6
11	Surface pretreatment and deposition temperature dependence of MgO epitaxy on GaN by thermal atomic layer deposition. Journal of Crystal Growth, 2020, 536, 125568.	1.5	6
12	Plasma enhanced atomic layer deposition of titanium nitride-molybdenum nitride solid solutions. Journal of Vacuum Science and Technology A: Vacuum, Surfaces and Films, 2021, 39, .	2.1	6
13	Byproduct-Free Route to Aminosiloxane Monolayers on Silicon/Silicon Dioxide. Langmuir, 2017, 33, 1639-1645.	3.5	3
14	Effects of growth substrate on the nucleation of monolayer MoTe <sub>2</sub> . CrystEngComm, 2021, 23, 7963-7969.	2.6	3
15	Surface characterization of ultrathin atomic layer deposited molybdenum oxide films using high-sensitivity low-energy ion scattering. Journal of Vacuum Science and Technology A: Vacuum, Surfaces and Films, 2021, 39, .	2.1	3
16	Exploiting Fixed Charge to Control Schottky Barrier Height in Si Al <sub>2</sub> O <sub>3</sub>  MoO <sub>x</sub> -based Tunnel Diodes. , 2021, , .		2
17	Ultrathin atomic layer deposited niobium oxide as a passivation layer in silicon based photovoltaics. Journal of Applied Physics, 2021, 130, 215301.	2.5	2
18	Plasma-enhanced atomic layer deposition of titanium molybdenum nitride: Influence of RF bias and substrate structure. Journal of Vacuum Science and Technology A: Vacuum, Surfaces and Films, 2021, 39, 053408.	2.1	1